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Contents

- vii Conference Committee
- ix Introduction

SESSION 1 POLARIZATION AND COHERENCE I

- 8171 02 Temporal and spectral degrees of polarization of light (Invited Paper) [8171-01]
 P. Réfrégier, Institut Fresnel, CNRS, Univ. d' Aix-Marseille, Ecole Centrale Marseille (France);
 T. Setälä, Aalto Univ. (Finland); A. T. Friberg, Aalto Univ. (Finland), Univ. of Eastern Finland (Finland), and KTH Royal Institute of Technology (Sweden)
- 8171 03 Random media confer high polarization degree to unpolarized light [8171-02]
 J. Sorrentini, M. Zerrad, G. Soriano, C. Amra, Institut Fresnel, CNRS, Univ. d' Aix-Marseille, Ecole Centrale Marseille (France)
- 8171 04 Evolution of vortex density in a non-diffracting speckle field with its continuous phase removed [8171-03]
 M. Chen, C. Dainty, National Univ. of Ireland, Galway (Ireland)
- 8171 05 Electromagnetic Hanbury Brown-Twiss phenomenon [8171-04]
 T. Hassinen, J. Tervo, Univ. of Eastern Finland (Finland); T. Setälä, Aalto Univ. (Finland);
 A. T. Friberg, Univ. of Eastern Finland (Finland), Aalto Univ. (Finland), and KTH Royal Institute of Technology (Sweden)
- 8171 06 **Further discussion of Huygens-Fresnel principle** [8171-05] Z. Liu, K. Uchikawa, Nikon Corp. (Japan)
- 8171 07 **Physical property of structural color in butterflies** [8171-06] M.-L. Lo, C.-C. Lee, National Central Univ. (Taiwan)

SESSION 2 POLARIZATION AND COHERENCE II

- 8171 08 About the nature of the coherence of light waves [8171-07]
 P. O. Demianenko, K. P. Demianenko, F. P. Demianenko, Y. F. Zinkovskiy, National Technical Univ. of Ukraine (Ukraine)
- 8171 0A Polarization modeling in square ring resonators with the consideration of output mirror's stress effect [8171-09]
 J. Yuan, X. Long, P. Zhang, Y. Wang, M. Chen, H. Yang, Z. Kang, National Univ. of Defense Technology (China)

SESSION 3 POLARIZATION AND COHERENCE III

- 8171 0B The Minimum Spanning Tree method applied to the study of optical speckle fields: spatial characterization of a Gaussian transition and its phase singularities [8171-10]
 O. Vasseur, I. Bergoënd, D. Upadhyay, X. Orlik, Onera The French Aerospace Lab. (France)
- 8171 OC **Multiscale spatial depolarization of light: electromagnetism and statistical optics** [8171-11] M. Zerrad, J. Sorrentini, G. Soriano, C. Amra, Institut Fresnel, CNRS, Univ. d' Aix-Marseille, Ecole Centrale Marseille (France)

SESSION 4 BEAM PROPAGATION

- 8171 OE **Tests for assessing beam propagation algorithms (Invited Paper)** [8171-13] B. D. Stone, Synopsys, Inc. (United States)
- 8171 OF Efficient use of grating theories with partially coherent illumination (Invited Paper) [8171-14] J. Tervo, H. J. Hyvärinen, T. Saastamoinen, I. Vartiainen, J. Turunen, Univ. of Eastern Finland (Finland)
- 8171 OH Gaussian beam mode analysis of optical pulses [8171-16] R. J. Mahon, J. A. Murphy, National Univ. of Ireland, Maynooth (Ireland)

SESSION 5 TOPICS IN MICROLITHOGRAPHY

8171 OK Numerical optimization of illumination and mask layout for the enlargement of process windows and for the control of photoresist profiles in proximity printing (Invited Paper) [8171-19]

K. Motzek, Fraunhofer Institute for Integrated Systems and Device Technology (Germany); S. Partel, Vorarlberg Univ. of Applied Sciences (Austria); U. Vogler, SUSS MicroOptics (Switzerland); A. Erdmann, Fraunhofer Institute for Integrated Systems and Device Technology (Germany)

- 8171 OL Illumination pupilgram prediction and control method in advanced optical lithography [8171-20]
 T. Matsuyama, N. Kita, Nikon Corp. (Japan); D. G. Smith, Nikon Research Corp. of America (United States)
- 8171 0M Predictive modeling of EUV-lithography: the role of mask, optics, and photoresist effects (Invited Paper) [8171-21]
 A. Erdmann, Fraunhofer Institute for Integrated Systems and Device Technology (Germany) and Friedrich-Alexander-Univ. Erlangen-Nürnberg (Germany); P. Evanschitzky, Fraunhofer Institute for Integrated Systems and Device Technology (Germany); F. Shao, Fraunhofer Institute for Integrated Systems and Device Technology (Germany) and Friedrich-Alexander-Univ. Erlangen-Nürnberg (Germany); T. Fühner, Fraunhofer Institute for Integrated Systems and Device Technology (Germany); G. F. Lorusso, E. Hendrickx, M. Goethals, R. Jonckheere, IMEC (Belgium); T. Bret, T. Hofmann, Carl Zeiss SMS GmbH (Germany)

8171 ON Analytical model for EUV mask diffraction field calculation [8171-22]

Y. Cao, X. Wang, Shanghai Institute of Optics and Fine Mechanics (China) and Graduate School of the Chinese Academy of Sciences (China); A. Erdmann, Fraunhofer Institute for Integrated Systems and Device Technology (Germany); P. Bu, Y. Bu, Shanghai Institute of Optics and Fine Mechanics (China) and Graduate School of the Chinese Academy of Sciences (China)

8171 00 Influence of geometry variations and defects on the near-field optical properties of pulsed compression gratings [8171-23]
 J. Wang, Shanghai Institute of Optics and Fine Mechanics (China); A. Erdmann, Fraunhofer Institute of Integrated Systems and Device Technology (Germany); S. Liu, J. Shao, Y. Jin,

H. He, K. Yi, Shanghai Institute of Optics and Fine Mechanics (China)

POSTER SESSION

- 8171 0Q Higher-order ghost imaging with partially polarized classical light [8171-26]
 H. Kellock, T. Setälä, Aalto Univ. (Finland); T. Shirai, National Institute of Advanced Industrial Science and Technology (Japan); A. T. Friberg, Aalto Univ. (Finland), Univ. of Eastern Finland (Finland), and KTH Royal Institute of Technology (Sweden)
- 8171 OR Corrected coupled-wave theory for non-slanted reflection gratings [8171-27]
 L. A. Estepa, C. Neipp, J. Francés, A. Márquez, S. Bleda, M. Pérez-Molina, M. Ortuño,
 S. Gallego, Univ. de Alicante (Spain)
- 8171 0S Self-disappearance of the frequency doubling of light in germanium-silicate patterns [8171-28]
 V. A. Smirnov, L. I. Vostrikova, A.V. Rzhanov Institute of Semiconductor Physics (Russian Federation)

Author Index

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- Polarization and Coherence I
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- 2 Polarization and Coherence II Andreas Erdmann, Fraunhofer-Institut f
 ür Integrierte Systeme und Bauelementetechnologie (Germany)
- 3 Polarization and Coherence III Kristian Motzek, Fraunhofer-Institut f
 ür Integrierte Systeme und Bauelementetechnologie (Germany)
- Beam Propagation
 Daniel G. Smith, Nikon Research Corporation of America (United States)
- 5 Topics in Microlithography
 Donis G. Flagello, Nikon Research Corporation of America (United States)

Introduction

We humbly invite you to make use of the materials presented in these proceedings of the Physical Optics Conference at the Optical Systems Design Symposium held in Marseille 2011. We hope that these materials will prove interesting and useful to you and your organizations.

The field of physical optics can encompass a huge array of subjects, from freespace scalar wave theory to electromagnetic field propagation through complex media. Today, a combination of highly developed and continually evolving theory, increasingly sophisticated algorithms, and powerful computational hardware is providing a deeper understanding of light and its interaction with matter in natural and engineered systems.

Like the subject itself, the papers within these proceedings cover a wide range of topics, methods, and theories loosely gathered together under the heading of Physical Optics. You'll find papers on various aspects of imaging in microlithography, scattered light and polarization, optical techniques for characterizing rough surfaces, new and clever methods for testing computational beam propagation, new perspectives on polarization and speckle, and much more.

As chair of this conference I owe its success to the invaluable input and assistance of my co-chairs Andreas Erdmann and Frank Wyrowski. Furthermore, we owe our thanks to our esteemed program committee who helped in soliciting these interesting papers, to the session chairs and authors who generously gave their time and energy to participate in our conference to the benefit of all, and to the many talented people at SPIE who worked so hard to make this symposium the success that it is. In general, we were pleased with the level of participation that we saw for our new conference, and we are encouraged enough to believe that the trend will continue at the next one.

Daniel G. Smith Frank Wyrowski Andreas Erdmann